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High Energy Small Focus Electron Sources

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EH-20

This electron source delivers a high power density beam into a small spot, for applications including evaporation, X-ray generation, thermal shocks, annealing, and detector testing.

Key features

- Energy range 1 keV to 20 keV
- Beam size (min.) <150 μm at low current and 150 mm WD and max. energy

Versions	EH-	EH-	EH-
	20-	20-	20-
	2	10	20
Beam current max.	100 μΑ	0.5 mA	1.0 mA



Not all parameters can be reached simultaneously. Above specifications may change without notice. Pictures / diagrams for reference only.

Characteristics

- Working distance 150 mm 750 mm
- Basic beam blanking (optional)
- Beam blanking, external (optional)
- Beam pulsing (optional)
- Differential pumping (DP) (optional)
- Advanced beam steering (patented)
- Parallel beam shift (optional)
- Computer control (optional)
- Magnetic shielding (optional)
- Beam scanning (optional)

 Microprocessor controlled beam current > Low Energy Electron regulation (optional) Remote control Sources > Electron Sources for RHEED > Accessories for Electron Typical Applications **Related Products** Sources > Ion Sources Electron beam treatment **Filaments** > X-ray Source Pre-mounted, pre-aligned **Detector testing** > Energy Analyzers & cathode units Evaporation **Imaging Energy** Complete service kit **Annealing** Filters Diagnostic box Desorption > Charged Particle Magnetic shielding for the beam **Detectors** Dissociation path > PEEM & IEEM Ionization of gases > UHV-Systems for X-ray shielding glass covers Cathodoluminescence Surface Analysis Fluorescent screens X-ray emission analyses > Packages for Scan amplifier X-ray generation Surface Analysis Faraday cups > Data Acquisition & Sample current measurement kit Instrument Control Software Gun control module

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